

**IN THE ABSTRACT**

Please amend the Abstract as follows.

**ABSTRACT OF THE DISCLOSURE**

~~There is provided an electron beam wiring technique which can correct deflection for a micro field used in electron beam writing equipment with high precision.~~

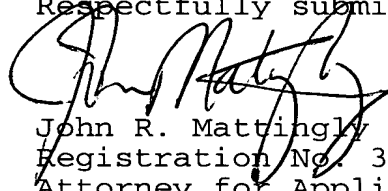
Electron beam writing equipment has an electron source, ~~and an electron optics system irradiating for scanning an~~ electron beam emitted from the electron source on a sample via deflection means having at least two different deflection speeds. ~~and an~~ An objective lens is used to form a desired pattern on the sample; ~~a stage mounting the sample; a mark for beam correction provided on the stage; an electron detector detecting a backscattered electron, a secondary electron or a transmission electron obtained by irradiation of the electron beam; a function moving the~~ The electron beam is moved by high speed scanning with the deflection means to repeat formation of a patterned beam. ~~a function moving the~~ The electron beam is moved on the mark for beam correction by low speed scanning with the deflection means in synchronization with one cycle of the repetition. ~~and a function detecting a backscattered electron or a secondary electron emitted from the mark for beam~~

~~correction and near it by the low speed scanning or a~~  
~~transmission electron transmitted through the mark for beam~~  
~~correction to correct the~~ The position or the deflection  
distance of the electron beam or blanking time is corrected  
using detectors for back scattered or secondary electrons ~~from~~  
~~the detected result.~~

**REMARKS**

Examination is respectfully requested.

Respectfully submitted,

A handwritten signature in black ink, appearing to read "John R. Mattingly", is written over the typed name and registration number.

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